

# PATENT ABSTRACTS OF JAPAN

(11)Publication number : **2001-042510**  
(43)Date of publication of application : **16.02.2001**

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(51)Int.CI.                    G03F 7/00  
                                B41N 1/14  
                                G03F 7/004  
                                G03F 7/11

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(21)Application number : **11-213586**                    (71)Applicant : **FUJI PHOTO FILM CO LTD**  
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## **(54) PHOTOSENSITIVE AND HEAT SENSITIVE RECORDING MATERIAL**

### **(57)Abstract:**

**PROBLEM TO BE SOLVED:** To ensure superior shelf stability and printing resistance by successively disposing a 1st layer having a polarity changing material which changes from a lipophilic material into a hydrophilic material under heat and a 2nd layer containing a water-insoluble and alkaline water-soluble polymer on a substrate.

**SOLUTION:** A 1st layer having a polarity changing material which changes from a lipophilic material into a hydrophilic material under heat and a 2nd layer containing a water-insoluble and alkaline water-soluble polymer are successively disposed on a substrate. Since the polarity changing material has high polarity changing ability, the penetrating property of a developing solution is considerably enhanced, developability is less liable to change due to preservation and the polarity changing material used on the interface of the substrate prevents the lowering of developability near the substrate and suppresses a change of sensitivity due to preservation. Since the polarity changing material is used in combination with the alkaline water-soluble polymer, shelf stability is enhanced without deteriorating printing resistance and satisfactory printing resistance is ensured.

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## **LEGAL STATUS**

[Date of request for examination]

[Date of sending the examiner's decision of rejection]

[Kind of final disposal of application other than the examiner's decision of rejection or application converted registration]

[Date of final disposal for application]

[Patent number]

[Date of registration]

[Number of appeal against examiner's decision of rejection]

[Date of requesting appeal against examiner's decision of rejection]

[Date of extinction of right]

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